2024년 1월 26일(금), 09:00-10:45
Room L(206),2층

Q. Metrology, Inspection, Analysis, and Yield Enhancement 분과

[FL1-Q] Metrology, Inspection, and Yield Enhancement II

좌장: 강상우 소장(한국표준과학연구원), 정용우 TL(SK 하이닉스)

초청발표 FL1-Q-1 09:00-09:30	반도체 계측 공정에서 영상 처리의 활용 이성일 DRAM Metrology Technology Team, Manufacturing Technology, SK hynix
초청발표 FL1-Q-2 09:30-10:00	A Zerogap Strain Sensor Mahsa Haddadi Moghaddam[1,2] and Dai-Sik Kim[1,2,3,4] [1]Department of Physics, UNIST, [2]Quantum Photonics Institute, UNIST, [3]Center for Angstrom Scale Electromagnetism, UNIST, [4]Department of Physics and Astronomy, Seoul National University
FL1-Q-3 10:00-10:15	Advancing Semiconductor Characterization: Dual Rotating Polarizers Ellipsometry Junho Choi, Jongkyoon Park, Sukhyun Choi, Yong Jai Cho, and Chegal Won Advanced Instrumentation Institute, KRISS
FL1-Q-4 10:15-10:30	AFM을 이용한 EUV Photoresist 프로파일 모니터링 김해리, 권광민, 최규진, 김규영 기반기술센터, 선행 Inspection 기술, SK hynix
FL1-Q-5 10:30-10:45	In-situ Monitoring of Contaminant Particles Generated during PECVD Process Using a Particle Beam Mass Spectrometer Seungjae Lee[1], Junggil Na[2], Kyunghwan Jung[2], and Taesung Kim[1,3] [1]Mechanical Engineering, Sungkyunkwan University, [2]JJ CNS, [3]SKKU Advanced Institute of Nano technology (SAINT), Sungkyunkwan University